

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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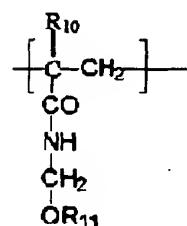
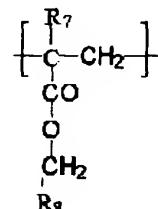
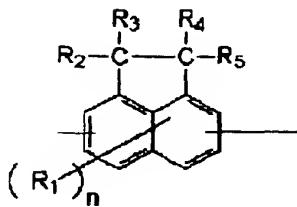
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TITLE : ANTIREFLECTIVE FILM-FORMING  
 COMPOSITION



ABSTRACT : PROBLEM TO BE SOLVED: To obtain an antireflective film-forming composition which is useful for the fine processing in lithography process using various kinds of radiation and is particularly suitable for the production of integrated circuit elements by incorporating a specific polymer having divalent groups and a solvent.

SOLUTION: This composition is obtained by incorporating a polymer having divalent groups shown by formula I (R1 is a monovalent atom or group; (n) is 0-4; R2 to R5 are each OH or a monovalent atom or group), a solvent, and preferably a curing agent as well as a copolymer having a structural unit shown by formula II (R7 is H or methyl; R8 is an alkyl or the like) and a structural unit shown by formula III (R10 is H or methyl; R11 is H or an organic group) and a film-forming ability.

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